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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
10/611,589	06/30/2003	B. Michelle Chen	AMAT/1717.D2/CPES/DT/PJS 5241	
7590 04/25/2006			EXAMINER	
Patent Counsel			WYSZOMIERSKI, GEORGE P	
APPLIED MATERIALS, INC. P.O. Box 450A			ART UNIT	PAPER NUMBER
Santa Clara, CA	A 95052		1742	
			DATE MAILED: 04/25/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)
	10/611,589	CHEN ET AL.
Office Action Summary	Examiner	Art Unit
	George P. Wyszomierski	1742
The MAILING DATE of this communicate Period for Reply	ion appears on the cover sheet with t	he correspondence address
A SHORTENED STATUTORY PERIOD FOR WHICHEVER IS LONGER, FROM THE MAIL - Extensions of time may be available under the provisions of 37 after SIX (6) MONTHS from the mailing date of this communic: - If NO period for reply is specified above, the maximum statutor - Failure to reply within the set or extended period for reply will, I Any reply received by the Office later than three months after the earned patent term adjustment. See 37 CFR 1.704(b).	ING DATE OF THIS COMMUNICAT CFR 1.136(a). In no event, however, may a reply lation. Ty period will apply and will expire SIX (6) MONTHS by statute, cause the application to become ABAND	TION. De timely filed from the mailing date of this communication. ONED (35 U.S.C. § 133).
Status		
 1) Responsive to communication(s) filed on 2a) This action is FINAL. 2b) Since this application is in condition for a closed in accordance with the practice upon 2b. 	☐ This action is non-final. allowance except for formal matters,	
Disposition of Claims		
4)	vithdrawn from consideration.	
Application Papers		
9) The specification is objected to by the Example 10) The drawing(s) filed on is/are: a)[Applicant may not request that any objection Replacement drawing sheet(s) including the 11) The oath or declaration is objected to by	accepted or b) objected to by to the drawing(s) be held in abeyance. correction is required if the drawing(s) is	See 37 CFR 1.85(a). s objected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for fa) All b) Some * c) None of: 1. Certified copies of the priority doc 2. Certified copies of the priority doc 3. Copies of the certified copies of the application from the International * See the attached detailed Office action for	uments have been received. uments have been received in Appli ne priority documents have been rec Bureau (PCT Rule 17.2(a)).	cation No eived in this National Stage
Attachment(s) Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-9) Information Disclosure Statement(s) (PTO-1449 or PTO-Paper No(s)/Mail Date		

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1. The Request for Continued Examination (RCE) filed March 22, 2006 (with Certificate of Mailing March 20, 2006) is considered proper. The Amendment filed February 21, 2006 has been entered. Prosecution continues as follows.

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 1, 5-9, 11-14, and 21-26 are rejected under 35 U.S.C. 103(a) as being unpatentable over the Sandhu et al. Advanced Metallization Conference reference in view of Kitazawa et al. (U.S. patent 6,178,623).

Sandhu discloses electroplating copper on a substrate followed by heat treating for 5 minutes in an atmosphere comprising nitrogen and hydrogen at a temperature of, e.g. 200 or 250 degrees C (see Figures 5 and 6 of Sandhu). With respect to the "first chamber" and "second chamber" limitations, it appears that Sandhu performs the annealing in a "Blue M inert gas oven" (see page 211 of Sandhu), which would be a chamber distinct from that in which the electroplating of Sandhu is performed.

Sandhu does not disclose rinsing prior to heat treating, does not specify bringing the substrate in proximity to a cooling plate to cool the substrate to a certain temperature as now claimed, does not specify a hydrogen content less than 4% as in instant claim 4, does not specify treating in an environment of less than 100 ppm oxygen as required by instant claims 8 and 13, and does not specify a pressure of 760 torr as required by claims 9 and 14. These

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differences are not seen as resulting in a patentable distinction between the prior art and the claimed invention because:

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- a) Kitazawa, particularly column 11, lines 23-26 therein, indicates it was conventional in the art, at the time of the invention, to rinse an electroplated copper layer prior to heat treatment in an inert atmosphere such as a nitrogen atmosphere.
- b) The temperatures to which the substrate is cooled in the instant claims, and at which the cooling plate is maintained in claims 23 and 26, include room temperature. The examiner's position is that any industrial process that involves heated material, such as those described by Sandhu, would include a final step of cooling the heated material to room temperature. Any apparatus involved in this step would be "maintained" at this temperature by virtue of its being exposed to ambient air.
- c) Sandhu performs annealing both in a substantially nitrogen atmosphere and in a 95% nitrogen-5% hydrogen atmosphere; see Figure 5 of Sandhu and its accompanying text. Thus, the use of an atmosphere between these two particular embodiments, e.g. one with less than 4% hydrogen, would fall within the purview of Sandhu.
- d) With respect to oxygen, page 211 of Sandhu emphasizes that the copper in the prior art readily reacts with oxygen and therefore it is important to anneal in a controlled, inert environment. Thus, use of a severely limited amount of oxygen as presently claimed would have been obvious from the Sandhu disclosure.
- e) Sandhu page 213 indicates that the oven used for heat treating in the prior art was not leak tight and operates only at 0.5 psi (26 torr) higher than atmospheric pressure (760 torr). This difference of approximately 3.4% in the pressure between the prior art and the claimed invention is held to be of no patentable moment.

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Consequently, the combined disclosure of Sandhu et al. together with that of Kitazawa et al. would have rendered the claimed invention obvious to one of ordinary skill in the art.

- 4. The terminal disclaimer filed on February 21, 2006 disclaiming the terminal portion of any patent granted on this application which would extend beyond the expiration date of any patent issued on Application no. 10/074,353 has been reviewed and is accepted. The terminal disclaimer has been recorded.
- 5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to George Wyszomierski whose telephone number is (571) 272-1252. The examiner can normally be reached on Monday thru Friday from 8:00 a.m. to 4:30 p.m. Eastern time.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Roy King, can be reached on (571) 272-1244. All patent application related correspondence transmitted by facsimile must be directed to the <u>new central facsimile number</u>, (571)-273-8300. This new Central FAX Number is the result of relocating the Central FAX server to the Office's Alexandria, Virginia campus.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

GEORGE WYSZŐMIERSKI PRIMARY EXAMINER GROUP 1789

GPW April 24, 2006